

# PATENT ABSTRACTS OF JAPAN

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(22)Date of filing :	<b>04.11.1982</b>	(72)Inventor :	<b>UMEDA YUKIO ISHII HARUO IKETANI MIKIO SONEDA SAKANOBU</b>

## (54) TREATMENT OF WASTE GAS

### (57)Abstract:

**PURPOSE:** To prevent the decrease in the oxidation and absorption power of a cleaning-up agent in a gas treatment cylinder by burning a metallic hydride to remove said hydride as an oxidized metal in the preceding stage of feeding waste gas from a reaction furnace to a blower.

**CONSTITUTION:** The waste gas in a reaction furnace 4 of a semiconductor production factory is sucked with a vacuum pump 5 and is fed to a burner 23, by which the metallic hydride in the waste gas is separated as an oxide from the waste gas, then the waste gas is fed through a filter 24 by a blower 3 into the lower part of a humidifier 1, where the gas is released into water from an air diffusion header 2. The waste gas humidified by passing upward the inside of the water is fed in a waste gas pipe 9 to a gas treatment cylinder 8 where the gas is cleaned up by the compsn. of a cleaning-up agent. The cleaned gas is released through a cyclone 10.

